



## Influence of Al fraction on the defect spectra of MOCVD grown

## $\beta$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub>

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## Abstract:

Beta phase gallium oxide ( $\beta$ -Ga<sub>2</sub>O<sub>3</sub>) is an ultra-wide bandgap (UWBG) semiconductor with advantages such as superior device figures of merit for both RF and high-voltage applications and high radiation hardness due to higher bond strength associated with smaller lattice constant. Alloying  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> with aluminum produces  $\beta$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> and is essential for heterostructurebased devices with higher radiation tolerance. These UWBG semiconductors and designed heterostructures are attracting interest for circuit and sensing applications in a harsh radiation environment. Critical to success in real-world applications, it is crucial to understand the defect states in  $\beta$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub>. The present study addresses the initial exploration of the defect characterization using conventional electrical characterization and deep-level thermal and optical based defect spectroscopies (DLOS, DLTS) on  $\beta$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> at varying alloy compositions and will be compared with the reported defect spectra on  $\beta$ -Ga<sub>2</sub>O<sub>3</sub>.

 $\beta$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> epitaxial layer was grown by MOCVD atop a commercially available  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> (010) Sn-doped EFG-grown substrates. The nominal Al mole fraction was 3,5,7 and 10%, confirmed by high-resolution x-ray diffraction. Ni Schottky diodes were fabricated on the  $\beta$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> epitaxial layer, and Ti/Al/Ni/Au ohmic contacts were deposited on the Sn-doped substrate. The average net ionized doping concentration for the series of samples from 3% to 10% Al were 1.2, 1.1, 1.0, and 0.8 × 10<sup>18</sup> cm<sup>-3</sup>, respectively. The Schottky barrier heights (SBH) for each sample were extracted from IPE measurements and were found to increase with Al composition; however, the calculated values of SBH were influenced by surface pinning. Compared to defect spectra on  $\beta$ -Ga<sub>2</sub>O<sub>3</sub>, the  $\beta$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> material demonstrated a higher defect concentration by 10-100 times. A total of five defect levels were measured, three by DLTS and two deeper defects by DLOS in each  $\beta$ -(Al<sub>x</sub>Ga<sub>1-x</sub>)<sub>2</sub>O<sub>3</sub> sample. Specific trends and detailed discussion on each defect states with dependence on Al composition will be discussed in the workshop.